

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	"20040072445"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 14:16
S2	0	"electrochemical mechanical polishing" "potential step"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:29
S3	14	"electrochemical mechanical polishing" "waveform"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 14:42
S4	0	"electrochemical mechanical polishing" "pulse\$1"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 14:44
S5	7	"electrochemical mechanical polishing" "pulsed"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 14:44
S6	45	"electrochemical mechanical polishing" (pulsed or pulse)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 15:23
S7	2	"6379223".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 15:05
S8	448	"electropolishing" and (pulse or pulsed)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:37
S9	18	"electrochemical mechanical planarization" (pulsed or pulse)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:00
S10	5	"electrochemical mechanical planarization" (waveform)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:00

S12	71	"electrochemical mechanical polishing" (basin or tank or reservoir or vessel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:34
S13	68	S12 @py>"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:32
S14	0	S12 @py<"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:30
S15	24	"electrochemical mechanical planarization" (basin or tank or reservoir or vessel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 10:09
S16	1520	"electropolishing" and (basin or reservoir or bath or tank or vessel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:39
S17	851	S16 @py<"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:38
S18	253	"electropolishing" and ((basin or reservoir or bath or tank or vessel) with electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:39
S19	144	S18 @py<"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/27 17:39
S20	6	"electrochemical mechanical planarization" @py<"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 10:10
S21	9	"electrochemical mechanical polishing" @py<"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 10:37

S22	1	electropolishing and "third potential"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 13:00
S23	0	electropolishing and "potential steps"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 10:38
S24	448	"electropolishing" and (pulse or pulsed)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 10:42
S25	163	S24 @py<"2002"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 10:42
S26	0	electropolish and "third potential"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 11:46
S27	10	electropolish and "third step"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 11:48
S28	0	electropolish\$3 and "third pulse"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 12:48
S29	0	"electrochemical planarization" and "third pulse"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 12:51
S30	20	"electrochemical planarization" and "pulse"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 12:51
S32	1	"third potential" and (205/640-685). ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 13:03

S33	6	"third pulse" and (205/640-685). ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 15:57
S39	2	"fourth pulse" and (205/640-685). ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	AND	OFF	2005/06/28 15:57